

Transmission Line Method

20164050 장재형

What is TLM?

TLM : Transmission Line **M**ethod or Transfer Length **M**ethod

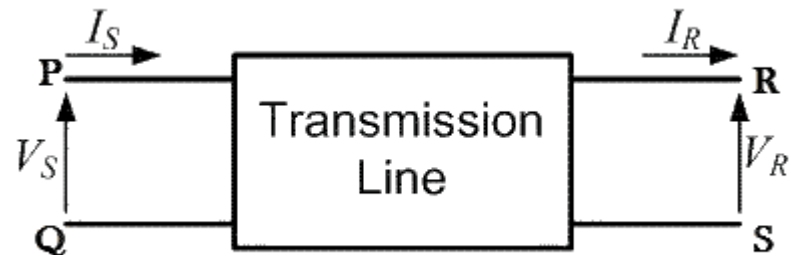
A method of calculating the contact resistance using a horizontal electrode.

Described by H.H. Berger's "Models for contacts to planar devices" Solid State Electronics, Vol. 15 pp. 145 (1972)

In 1970s, it was widely known that a mathematical calculation was made by constructing an equivalent circuit similar to a transmission line. → introduced to analyze electrical contact of semiconductors → TLM



Transmission line picture



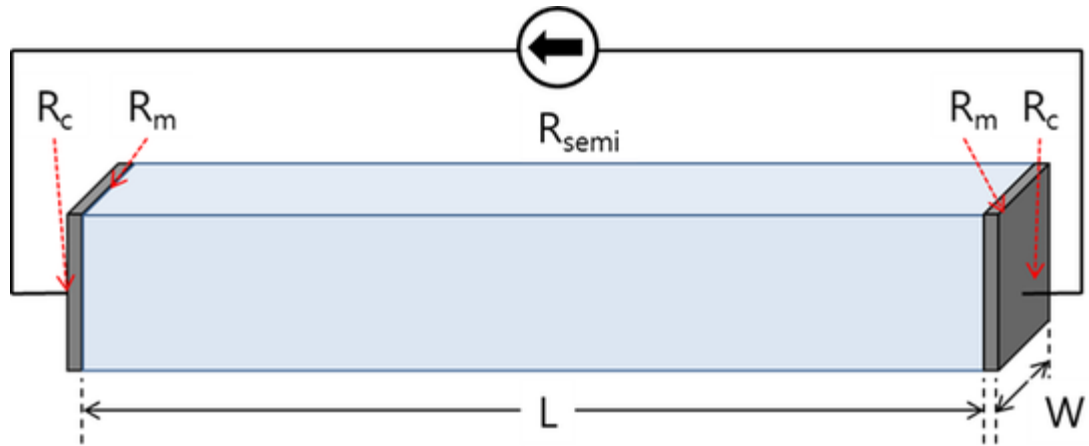
Transmission line equivalent circuit

Principles of TLM measurement

Ignored in most cases

$$R_T = 2R_m + 2R_c + R_{semi}$$

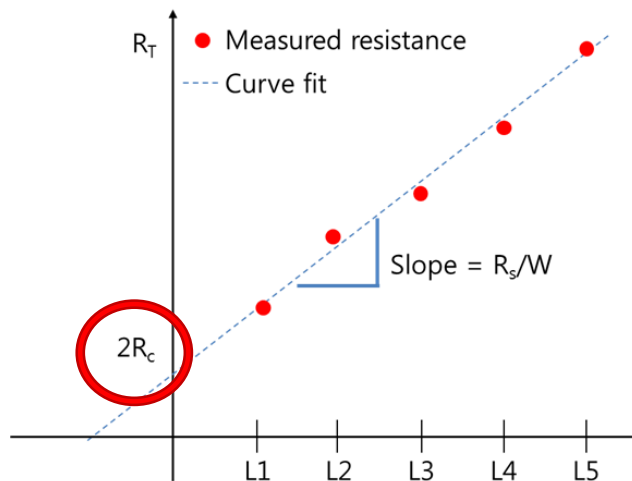
$$R_{semi} = R_s \frac{L}{W}$$



Simple resistor geometry (vertical contact)

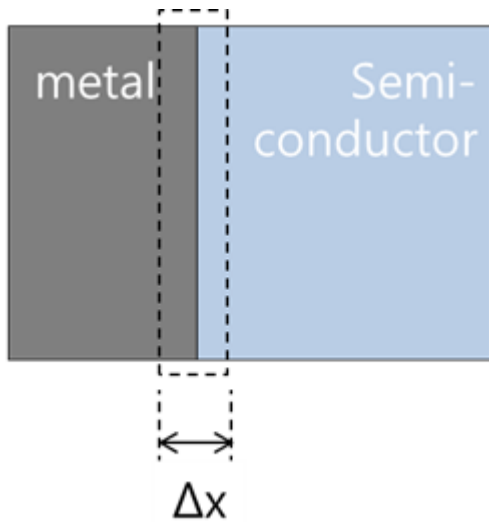


$$R_T = \frac{R_s}{W} L + 2R_c$$



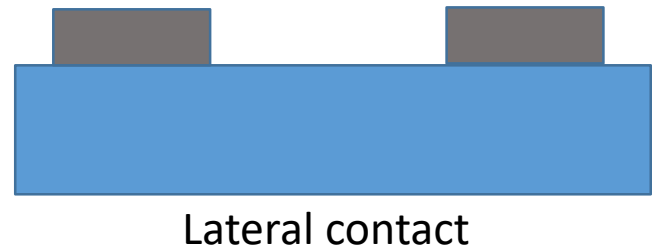
TLM measurement graph

Contact resistivity



$$R_c = \rho' \frac{\Delta x}{A_c}$$

$$\rho_c = \lim_{\Delta x \rightarrow 0} (\rho' \Delta x) = R_c A_c \quad (\text{Generally } 10^{-3} \sim 10^{-8} \Omega \cdot \text{cm}^2)$$



Lateral contact geometry & current crowding

$$I(x) \propto \exp\left(-\frac{x}{L_T}\right)$$

$$L_T = \sqrt{\frac{\rho_c}{R_s}}$$

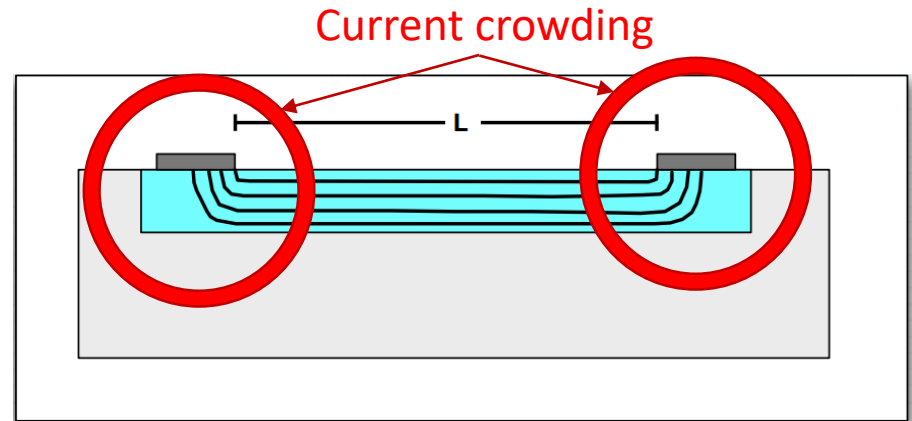
➔ Effective area of contact $A_c = L_T \cdot W$

We know $\rho_c = R_c A_c$,

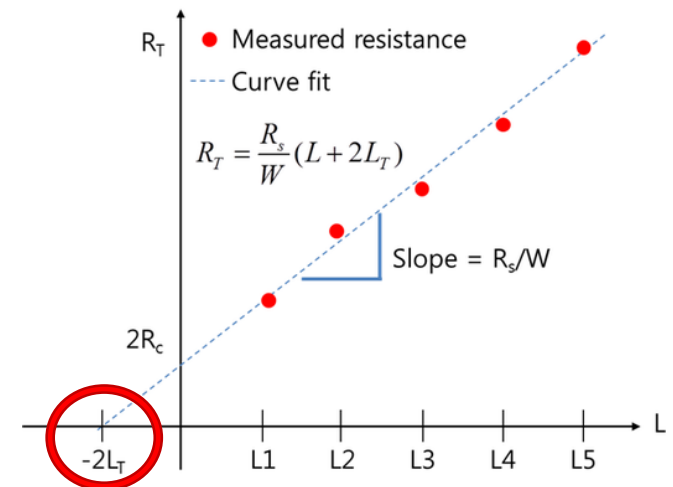
$$R_c = \frac{\rho_c}{L_T W} = \frac{R_s L_T}{W} \quad \Rightarrow \quad R_T = \frac{R_s}{W} L + 2R_c$$

$$= \frac{R_s}{W} L + \frac{2R_s L_T}{W}$$

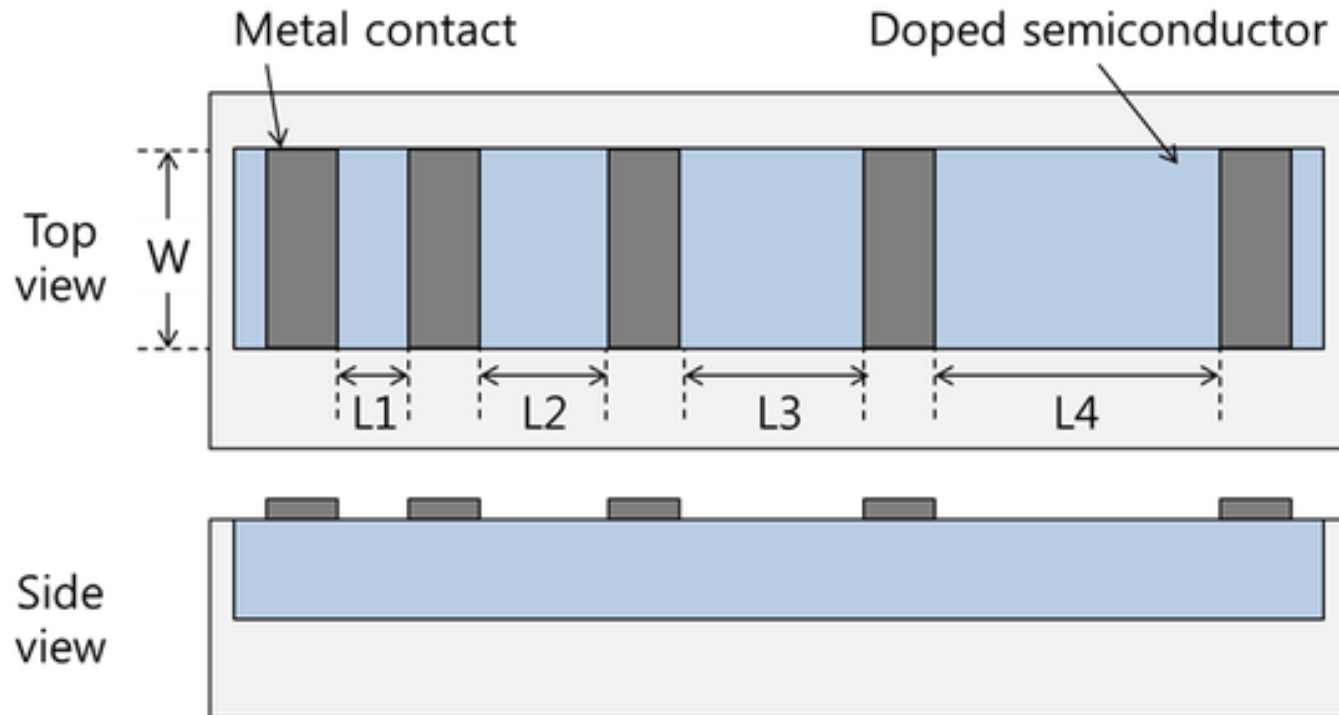
$$= \frac{R_s}{W} (L + 2L_T)$$



Lateral contact geometry

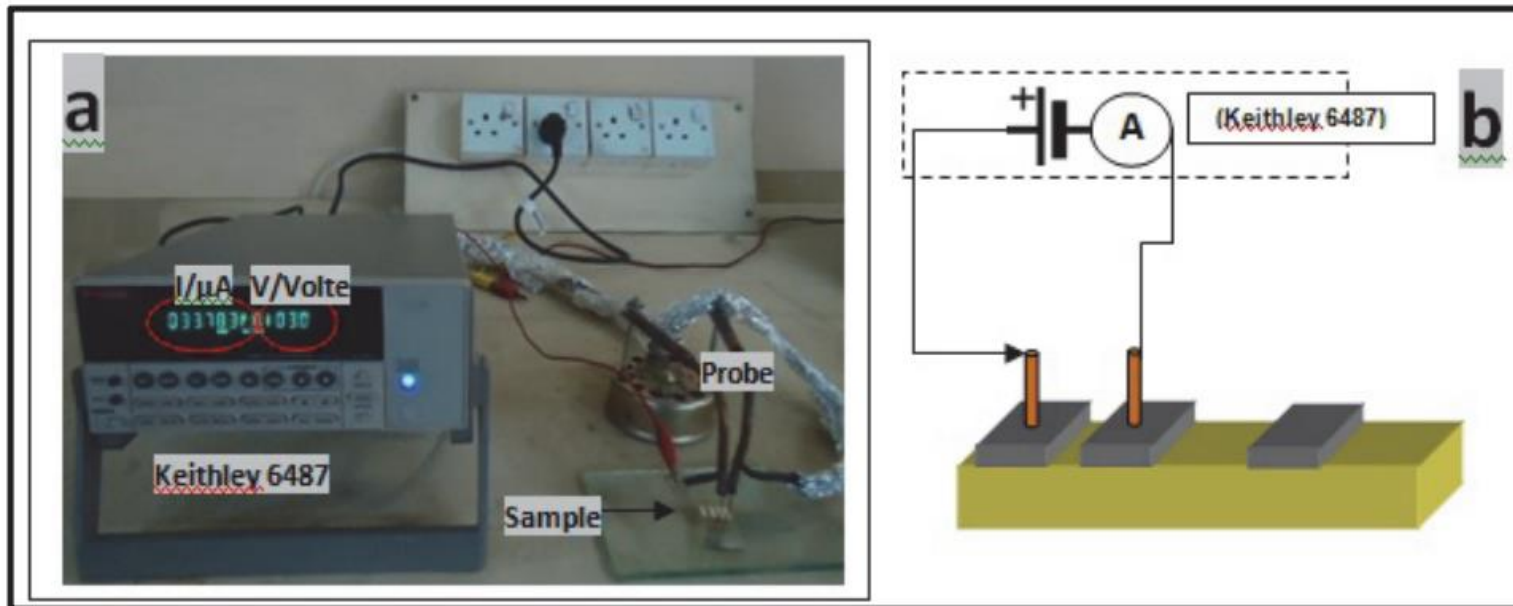


TLM test pattern



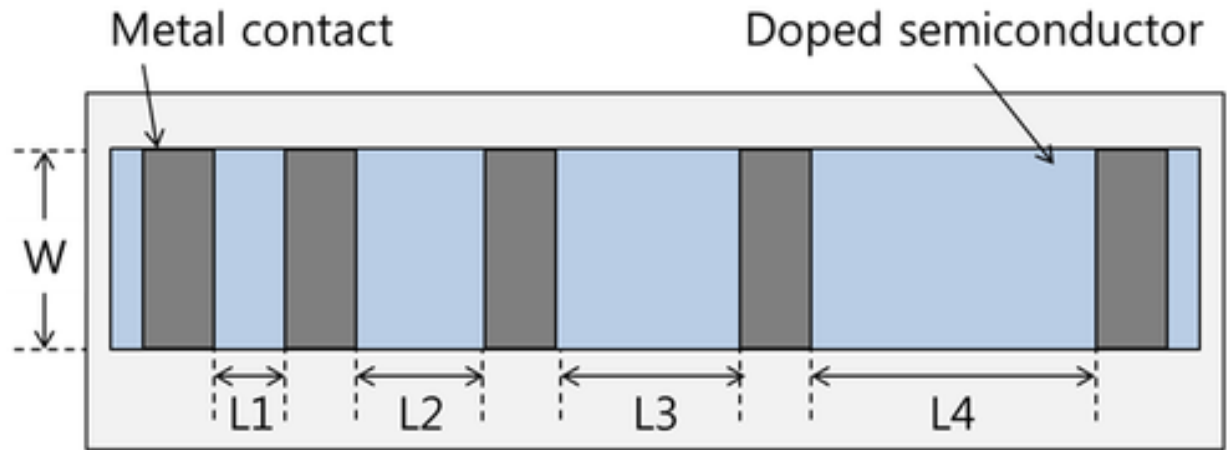
Example

- Measurement



Example

- Calculation



$W = 100\mu\text{m}$,

$L = 10\mu\text{m}, 20\mu\text{m}, 40\mu\text{m}, 80\mu\text{m}, 160\mu\text{m}$

Measurement results give the following resistances:

$R_1 = 7.59 \Omega, R_2 = 8.26 \Omega, R_3 = 9.85 \Omega, R_4 = 13.02 \Omega, R_5 = 18.87 \Omega$

$$R = 6.829 \Omega + (0.0756 \Omega/\mu\text{m})L$$

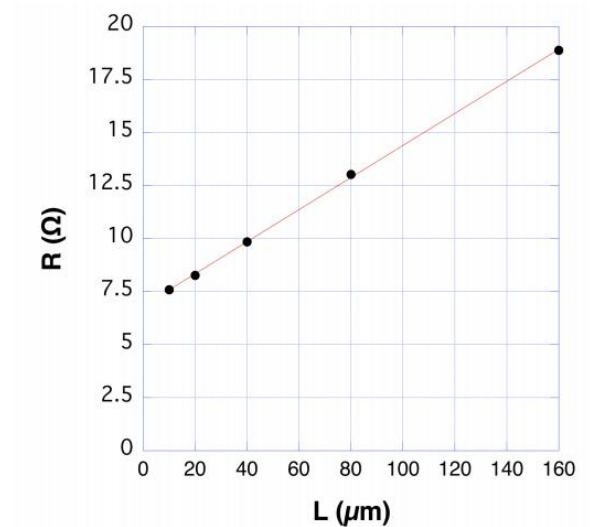
$$R_c = 6.829/2 \Omega = 3.415 \Omega$$

$$R_s = \text{slope} \times W = 0.0756 \Omega/\mu\text{m} \times 100 \mu\text{m} = 7.56 \Omega/\square$$

$$0 = 6.829 \Omega + (0.0756 \Omega/\mu\text{m})(-2L_T)$$

$$L_T = 6.829 \Omega / (2 \times 0.0756 \Omega/\mu\text{m}) = 45.2 \mu\text{m}$$

$$\rho_c = R_c L_T W = (3.415 \Omega)(0.00452 \text{ cm})(0.01 \text{ cm}) = 1.54 \times 10^{-4} \Omega \cdot \text{cm}^2$$



Reference

- S.S. Cohen “Contact resistance and methods for its determination, Thin Solid Films, 104, 361 (1983)
- D.K. Schroder, Semiconductor material and device characterization, Wiley, New York, 1998
- T. Abbas* , L. Slewa , Transmission line method (TLM) measurement of (metal/ZnS) contact resistance, 2015

Q&A